

AMENDMENTS TO THE CLAIMS

1-6. (Cancelled)

7. (Currently Amended) A platemaking method of a lithographic printing plate, comprising developing an exposed lithographic printing plate precursor with a developer, wherein the exposed lithographic printing plate precursor is obtained by an image recording method comprising imagewise exposing a lithographic printing plate precursor with an imaging time per pixel of 1 millisecond or less using a laser light with an emission wavelength selected from 405 nm and 375 nm ~~of from 250 nm to 420 nm~~, wherein the lithographic printing plate precursor comprises a support and an image recording layer, in which the image recording layer contains (A) a polymerization initiator and (B) a polymeric compound and is photosensitive in a wavelength of from 250 nm to 420 nm;

wherein the developer is a non-alkaline developer having a pH value of 10 or less.

8. (Original) The platemaking method according to claim 7, wherein the support has an anodized film with sealed micropores on the surface.

9. (Cancelled)

10. (Previously Presented) The platemaking method according to claim 7, wherein the image recording layer further contains (C) a binder polymer.

11. (Original) The platemaking method according to claim 10, wherein the binder polymer (C) does not have an acid group.

12. (New) The platemaking method according to claim 7, wherein the exposure is carried out using an optical system comprising: a DMD or GLV modulation element; and a semiconductor laser with a wavelength of 405 nm or 375 nm.

13. (New) The platemaking method according to claim 7, wherein the developer comprises an organic solvent.

14. (New) The platemaking method according to claim 7, wherein the developer comprises a nonionic surfactant.

15. (New) The platemaking method according to claim 7, wherein the developer comprises an anionic surfactant.

16. (New) The platemaking method according to claim 7, wherein the developer comprises a water-soluble polymeric compound.